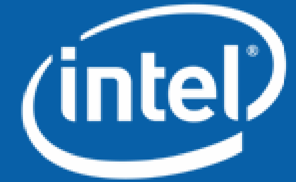
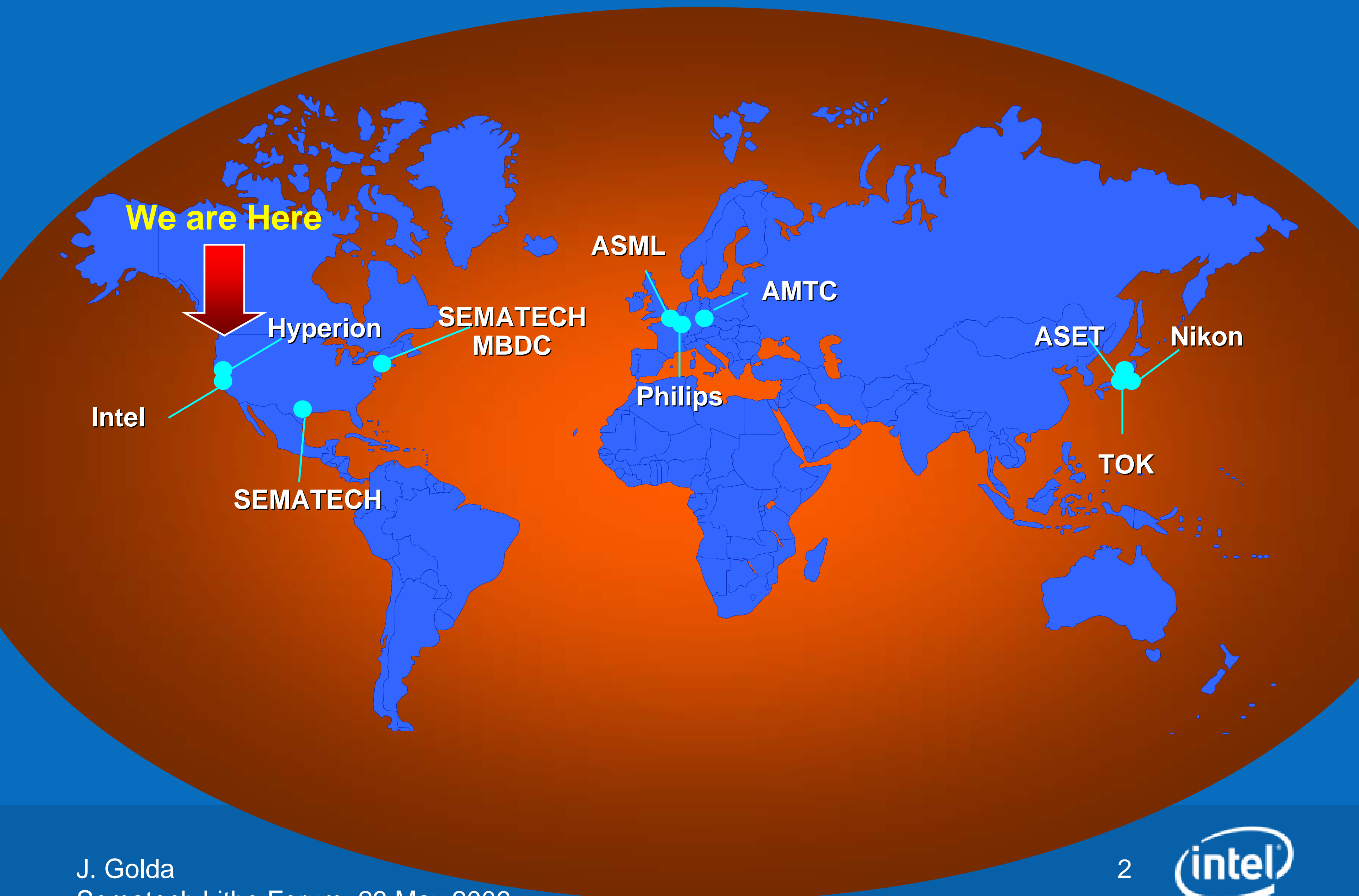


Sematech Lithography Forum: EUV Session Introduction

Janice Golda

Director, Litho Capital Equipment Development

Welcome to the EUV Session



EUV Critical Issues

- **Critical issues**
  - Resist resolution, sensitivity, and LER (#3 last year)
  - Collector lifetime (#2 last year)
  - Defect free mask (#1 last year)
  - Source power

- **Other remaining issues**
  - Reticle protection during storage, handling, and uses
  - Projection and illuminator optics quality and lifetime

- **Most significant concern is the timing and cost / business case for EUVL development**

Keep these in mind when listening to the presenters…

The Presenters

Industry Efforts…

SEMATECH & Other Consortia EUV Programs - Stefan Wurm

Exposure Tools…

ASML EUV Demo Tool Development and Status - John Zimmerman

Nikon EUV Tool Development Progress Summary - Takaharu Miura

EUV Source Development Progress - Joseph Pankert, Philips

EUV Optics Contamination - Iwao Nishiyama, ASET

The Presenters

Resist…

Resist Development Status for EUVL - Hiroto Yukawa, TOK

Reticles…

EUV Reticle Handling - Kevin Orvek, Intel

EUV Mask Blank Development - David Krick, SEMATECH

EUV Mask Patterning - Jan-Hendrick Peters, AMTC

What's Next…

EUV Extensibility - Russell Hudyma, Hyperion Development LLC